

ROUNDTABLES

To navigate between floors on Remo, use the numbered buttons on the left-hand side of the screen. Whilst Floor 1 acts as the Exhibitors Area, Floors 2-5 will contain the hosted roundtables, as below. Each roundtable has a number, which will match table number within the Remo platform. To join a table, double click on it. There is a maximum of 8 people per table, host included, and this is a first come first serve system. There will be 2 rotations of roundtables on each day.

FLOOR 2	FLOOR 3	FLOOR 4	FLOOR 5
<p>Roundtable 1 – Key Lessons and Considerations in UPW and HUPW Distribution Shutdown and Restart James Lee, Samsung Austin Semiconductor</p>	<p>Roundtable 10 – Design for Maintenance & Operation Principles in UPW Systems – End User Perspective Alana Denning, Page/imes</p>	<p>Roundtable 19 – New Challenges of Specialty Waste Treatment Systems Alan Knapp, Evoqua</p>	<p>Roundtable 27 – AMC Metrology Peng Sun, ChemTrace, A Business Unit of UCT</p>
<p>Roundtable 2 – Ion Exchange Resin Management: Lifetime, Triggers, Operations, Strategy Varinder Malik, Samsung Austin Semiconductor</p>	<p>Roundtable 11 – Ultrapure Water Sequences – What's on second? Chuck Dale, Suez</p>	<p>Roundtable 20 – Best Practices for POU Scrubber Wastewater Management Zachary Boswell, Samsung Austin Semiconductor</p>	<p>Roundtable 28 – AMC – Fab & Tool Environment Walter Den, Texas A&M University-San Antonio</p>
<p>Roundtable 3 – UPW Sampling and Lab Testing: How Often, Which Samples, What Parameters, Methods? Maohua Pan, Air Liquide Electronics</p>	<p>Roundtable 12 – The impact of over stated tool requirements on fab support system design FTD Solutions</p>	<p>Roundtable 21 – Fab tool water optimization and reclamation Jim Snow, SCREEN SPE</p>	<p>Roundtable 29 – AMC – FOUF & Mini-Environment Latif Ahmed, Intel</p>
<p>Roundtable 4 – Next Generation Particle Metrology for UPW for Particle Pre-Cursor Measurement Gary Van Schooneveld, CT Associates</p>	<p>Roundtable 13 – Chemicals – Sampling and Analysis of in-line and end-of-line Ultra High Performance Chemicals Florian Adler, Tiger Optics</p>	<p>Roundtable 22 – Instrumentation Selection in Wastewater Victoria Yun, Samsung Austin Semiconductor</p>	<p>Roundtable 30 – Critical Component Analysis Surjany Russell, ChemTrace, A Business Unit of UCT</p>
<p>Roundtable 5 – New Challenges to Ultrapure Water Filtration Jochen Ruth & Gerd Hesser, Pall</p>	<p>Roundtable 14 – Ultra High Performance Chemical Distribution and Blending David Kandiyeli, Mega Fluid Systems</p>	<p>Roundtable 23 – SEMI C98 – Guide for Treatment of Reuse Water in Semiconductor Processing Paul Kerr, Intel</p>	<p>Roundtable 31 – Filter Rating and Testing – What does it mean? Ryan Pavlick, Intel</p>
<p>Roundtable 6 – Physics of the particle vs. high-molecular-weight dissolved organic Steve Kosier, Kanomax FMT</p>	<p>Roundtable 15 – Chemicals – Supply Chain Challenges and the Cost of Quality Archita Sengupta, Intel</p>	<p>Roundtable 24 – Selection of Piping Materials for Wastewater Collection Systems and Hydrogen Peroxide in Wastewater Casey Williamson, Semtec</p>	<p>Roundtable 32 – Prefabrication Preassembly Modularization and Offsite Fabrication: The IKEA Concept John Painter, Pure Facilities Solutions</p>
<p>Roundtable 7 – “Real” Particle Concentration in UPW Unknown? Discussion on different state of the art particle metrologies Maria Pia Herrling, Ovivo</p>	<p>Roundtable 16 – Filtration for UHP Chemicals – Which filter is which and where do I use it? Ashutosh Bhabhe, Entegris</p>	<p>Roundtable 25 – HF treatment – Lime or CaCl₂ - which is best for me? Luke Wilson & Stephanie Lopez, Samsung Austin Semiconductor</p>	<p>Roundtable 33 – Operations in the time of Pandemic Brad Herbert, ON Semiconductor</p>
<p>Roundtable 8 – Evaluating UPW System Capacity and Minimizing Upgrade Scope Dave Buesser, FTD Solutions</p>	<p>Roundtable 17 – High Purity Chemicals for Advanced Technology Kevin Prettyman, GLOBALFOUNDRIES</p>	<p>Roundtable 26 – Azoles Treatment Mikael Khan, Arvia Technology</p>	<p>Roundtable 34 - H₂O₂ in Wastewater – When do I need to worry? FTD Solutions</p>
<p>Roundtable 9 – What is new in UPW membrane technology? Denise Haukkala, DuPont</p>	<p>Roundtable 18 – Chemical Particles <20nm: How to pick the right filter and detection challenges Anthony Ozzello, Entegris</p>		